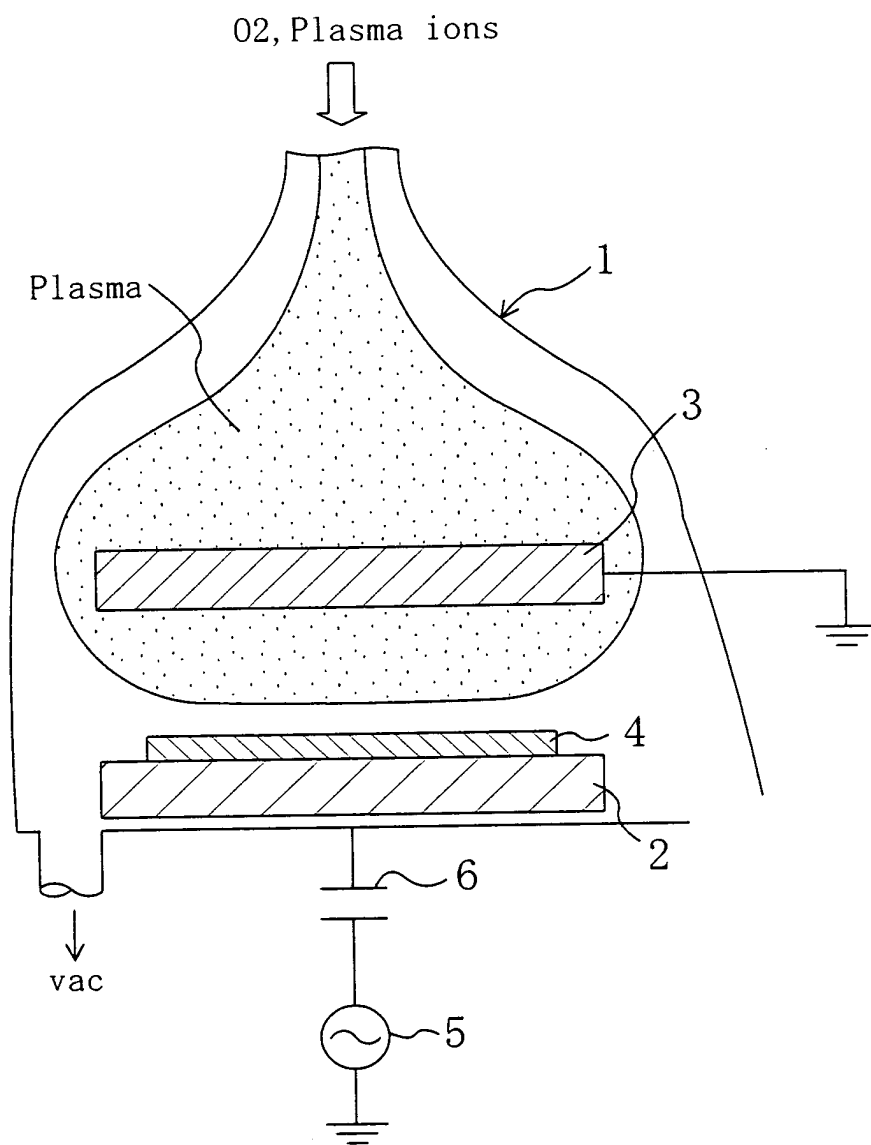


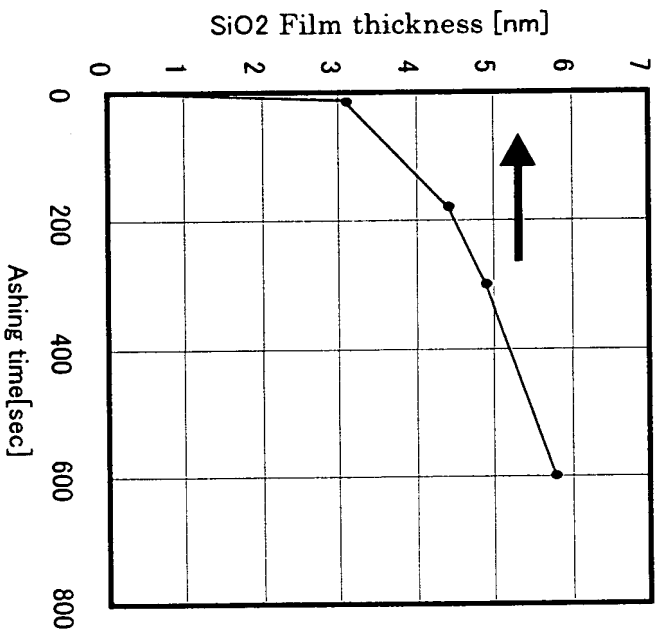
Fig. 1



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Fig.2(a)

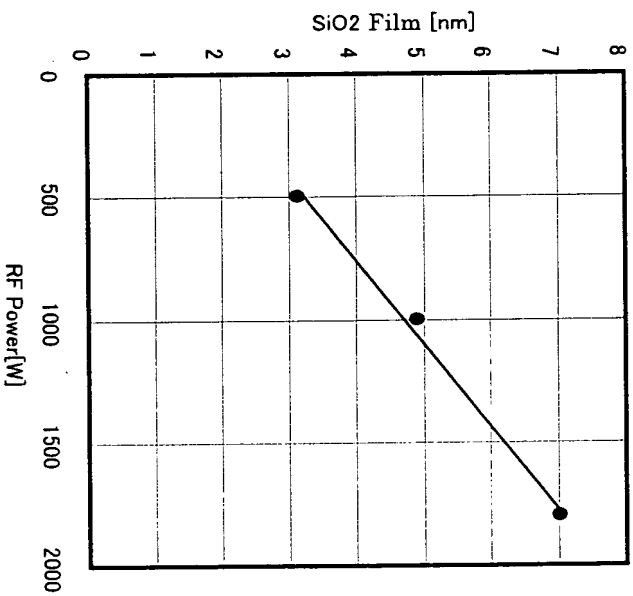
Dependency of film thickness on plasma time



High frequency power [W]	1000
Pressure [pa]	66
Oxygen flow rate [ml/min]	800
Temperature [°C]	180
Time [sec]	Y

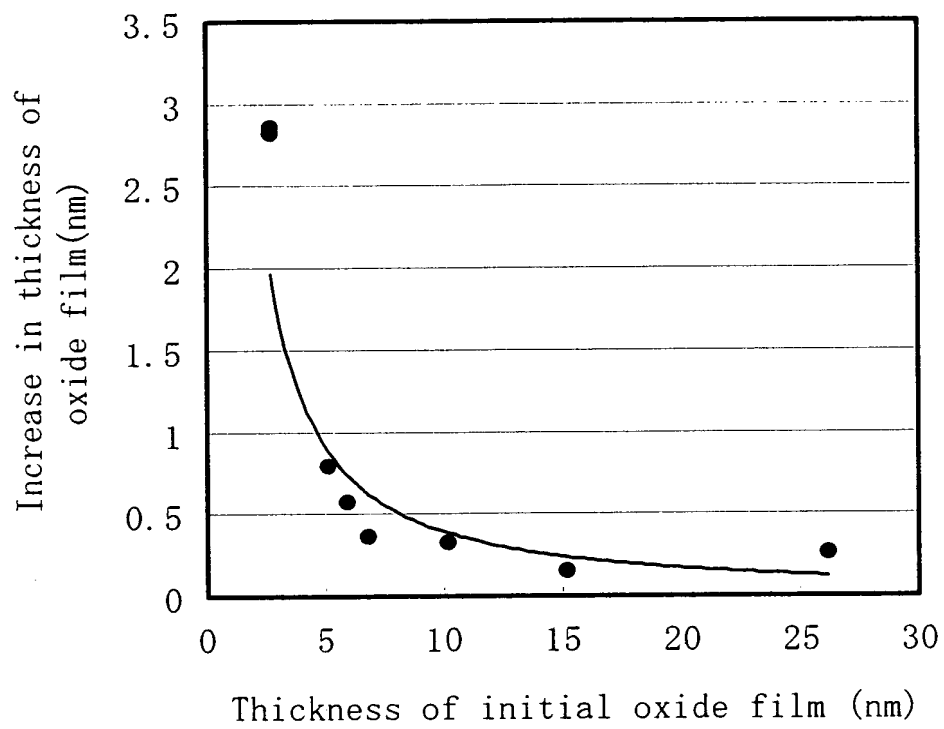
Fig.2(b)

Dependency of film thickness on bias

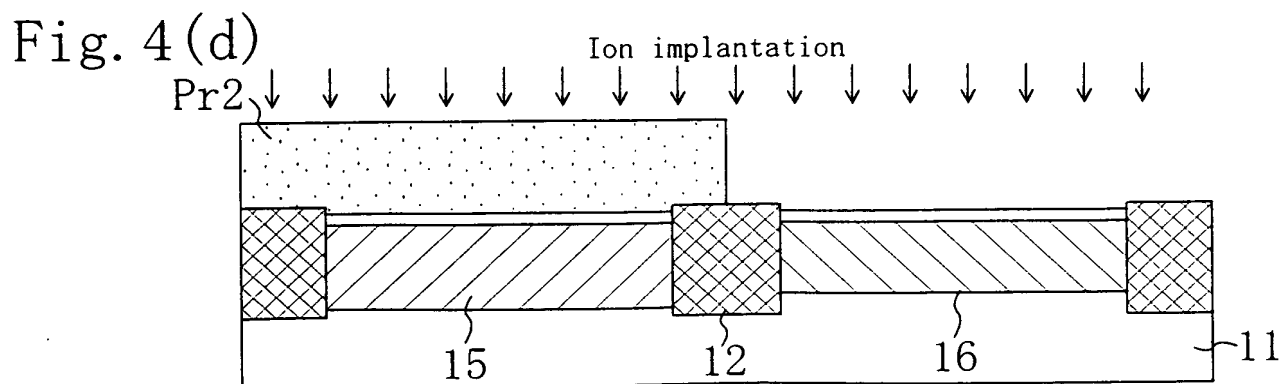
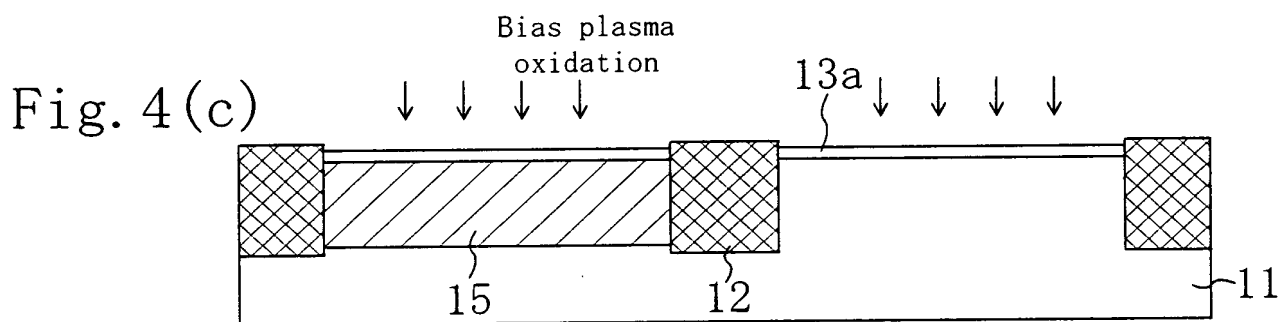
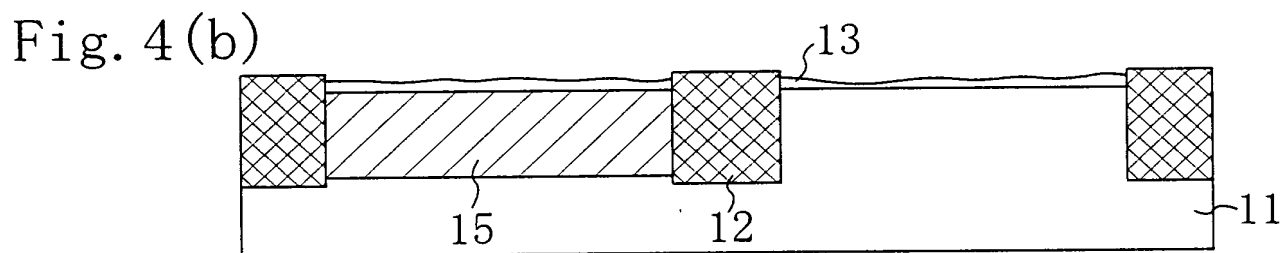
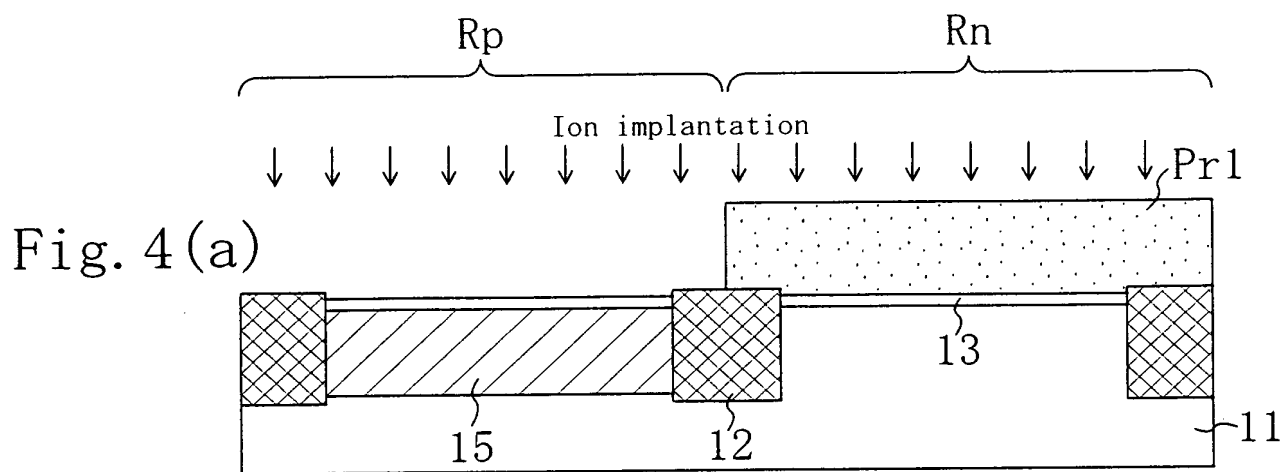


Conditions			
O2	800[ml/min]	800[ml/min]	800[ml/min]
RF Power	500[W]	1000[W]	1800[W]
Temp	180[°C]	180[°C]	180[°C]
Time	5[min]	5[min]	5[min]

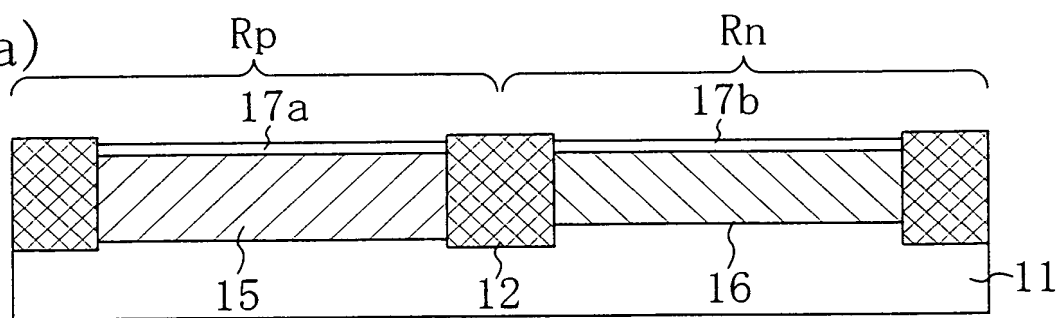
Fig. 3



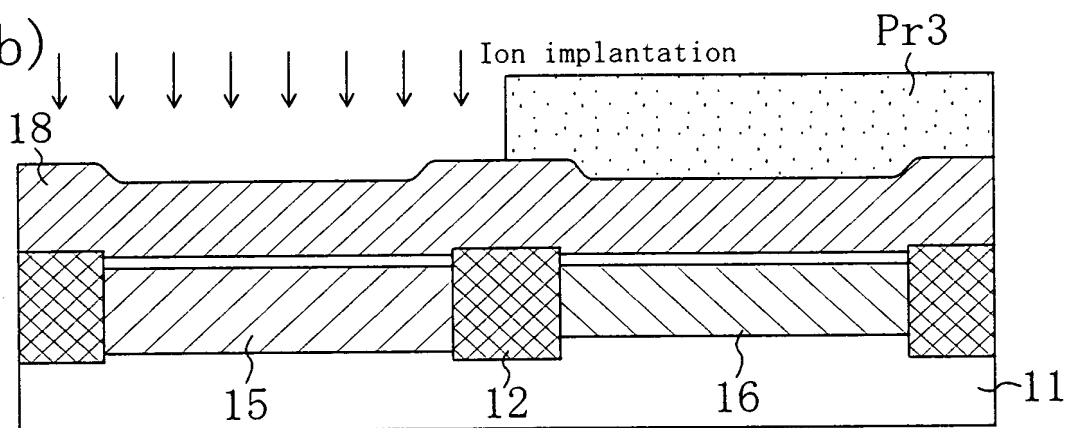
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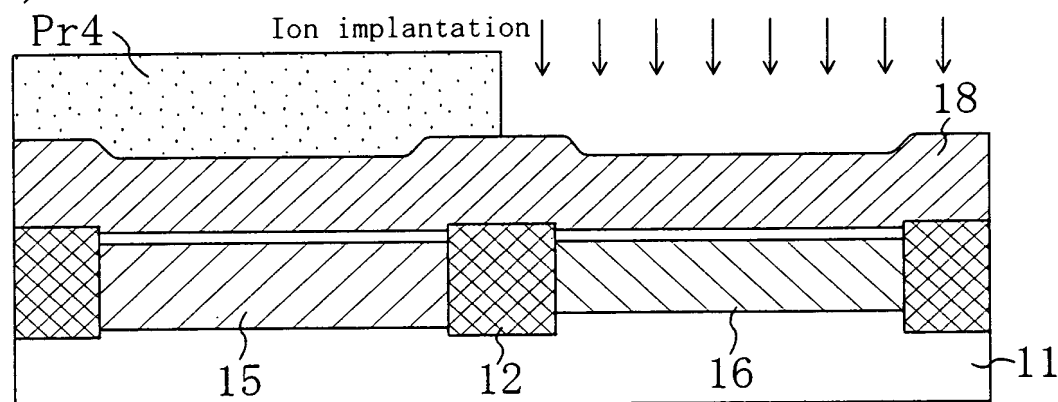
Rn



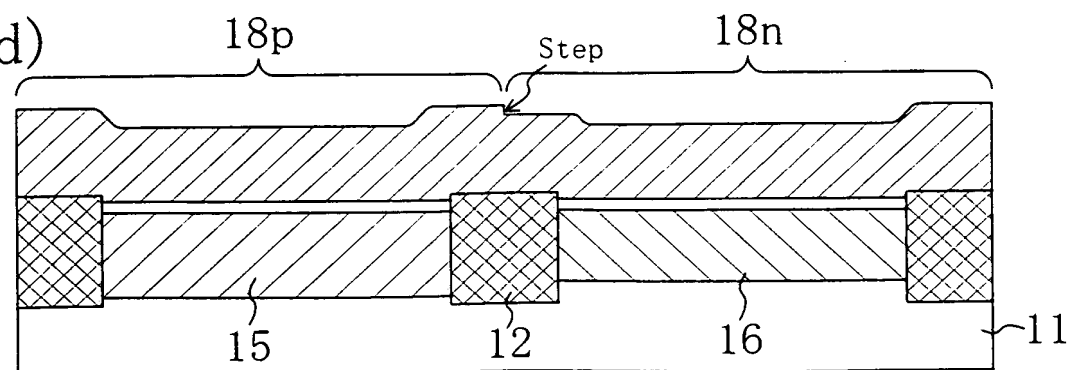
## Ion implantation



## Ion implantation



18p



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Fig. 6(a)

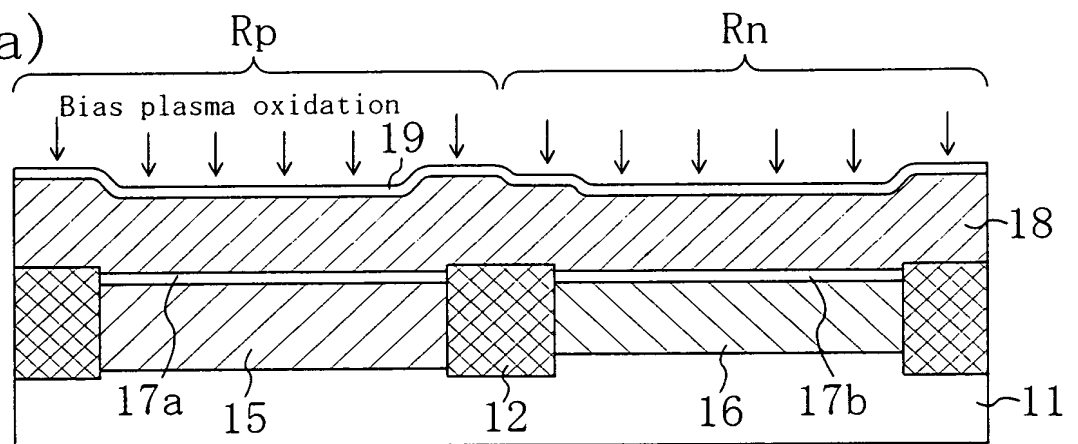


Fig. 6(b)

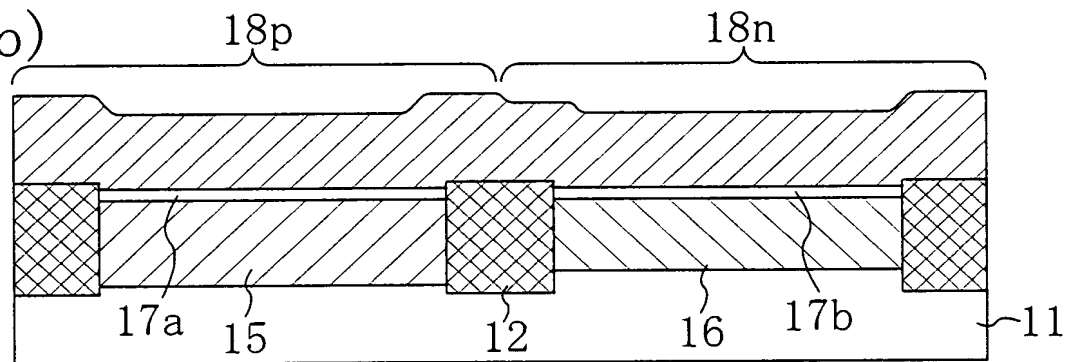


Fig. 6(c)

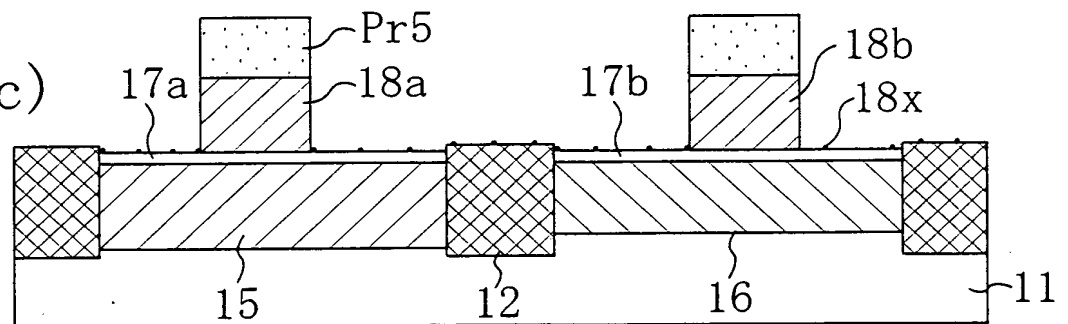


Fig. 6(d)

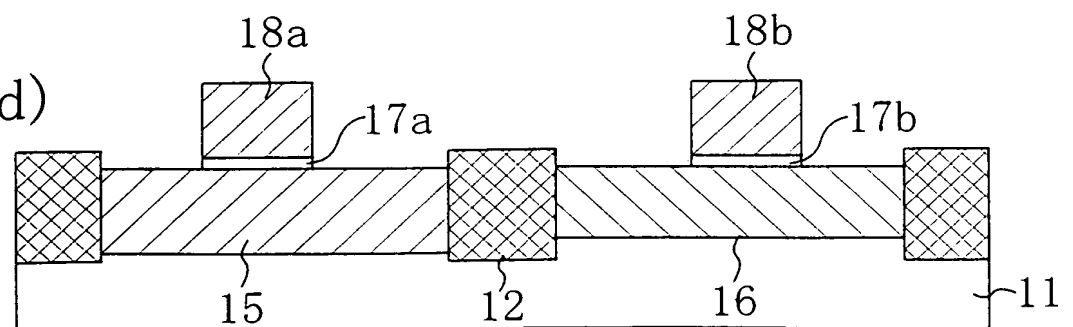


Fig. 7(a)

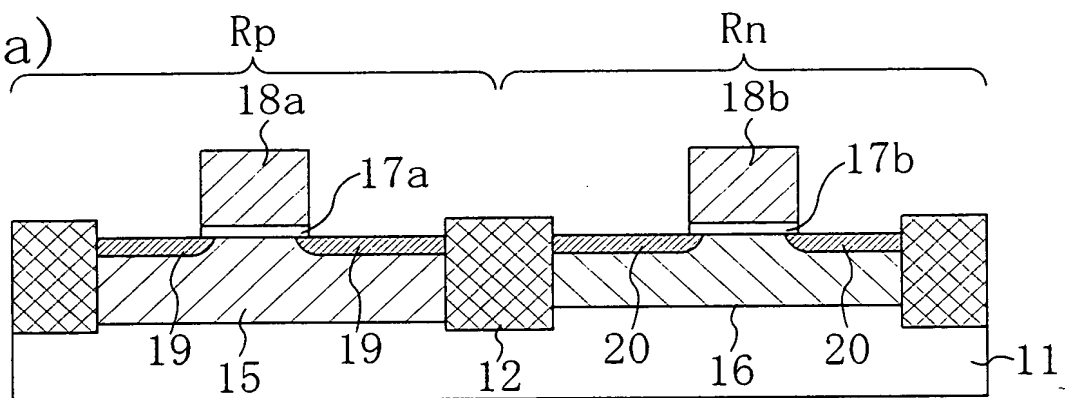


Fig. 7(b)

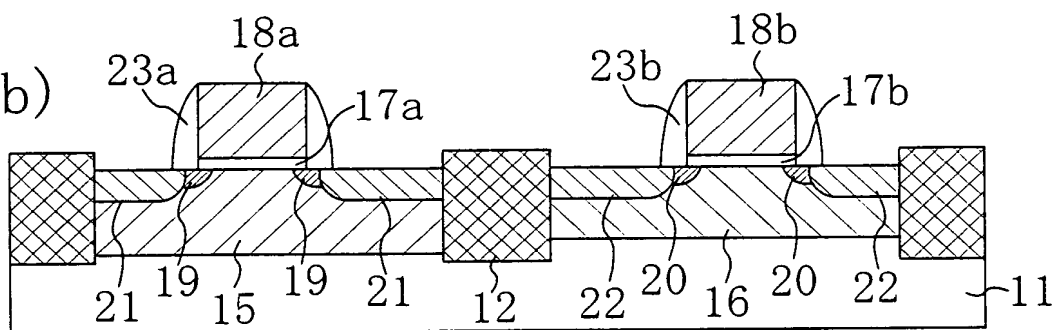


Fig. 7(c)

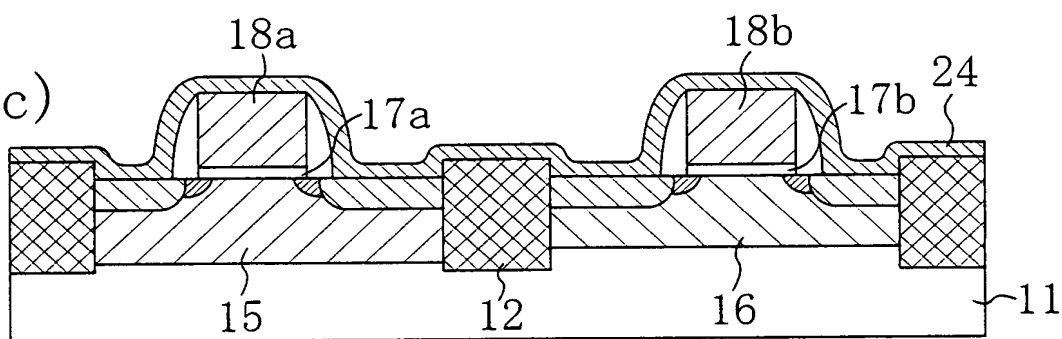
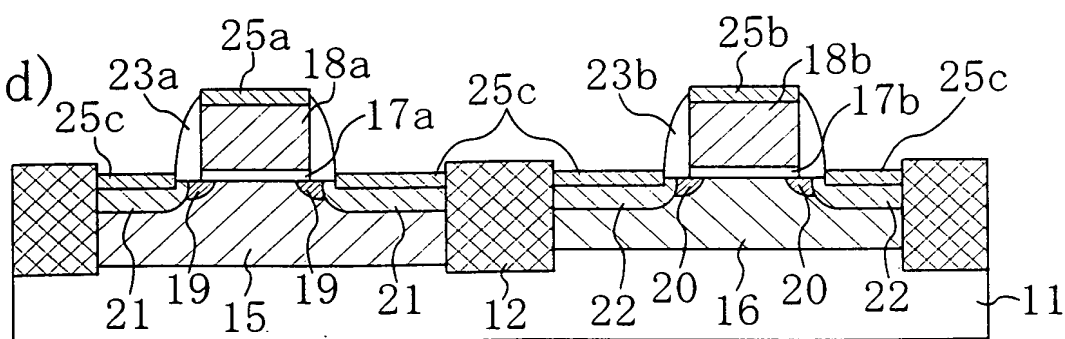


Fig. 7(d)



66pa/800mtorr/180°C/3min

Fig. 8(c)

sl.23 (No implantation)

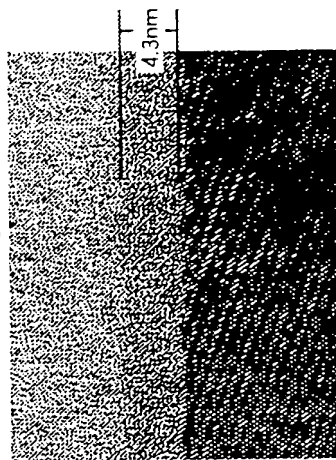


Fig. 8(b)

sl.22 (Pch)

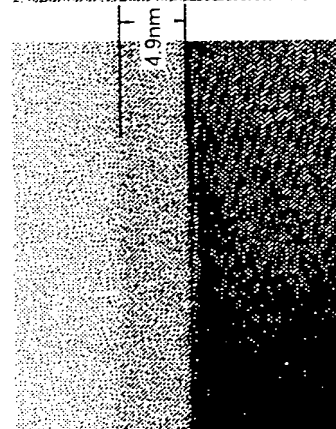
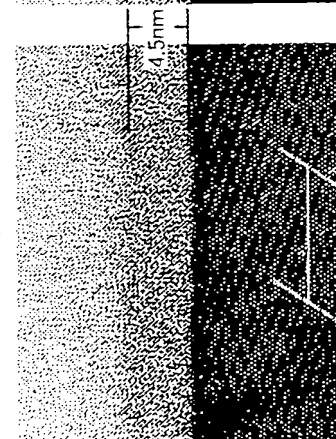


Fig. 8(a)

sl.21 (Nch)



On Si substrate

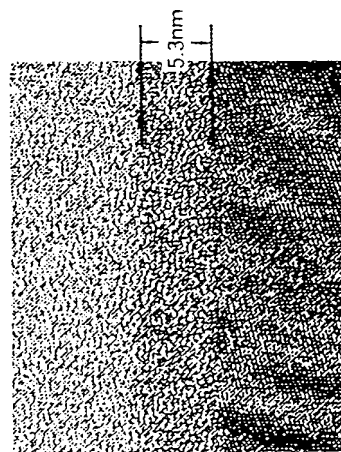


Fig. 8(e)

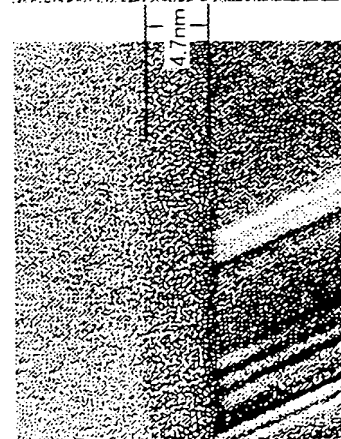


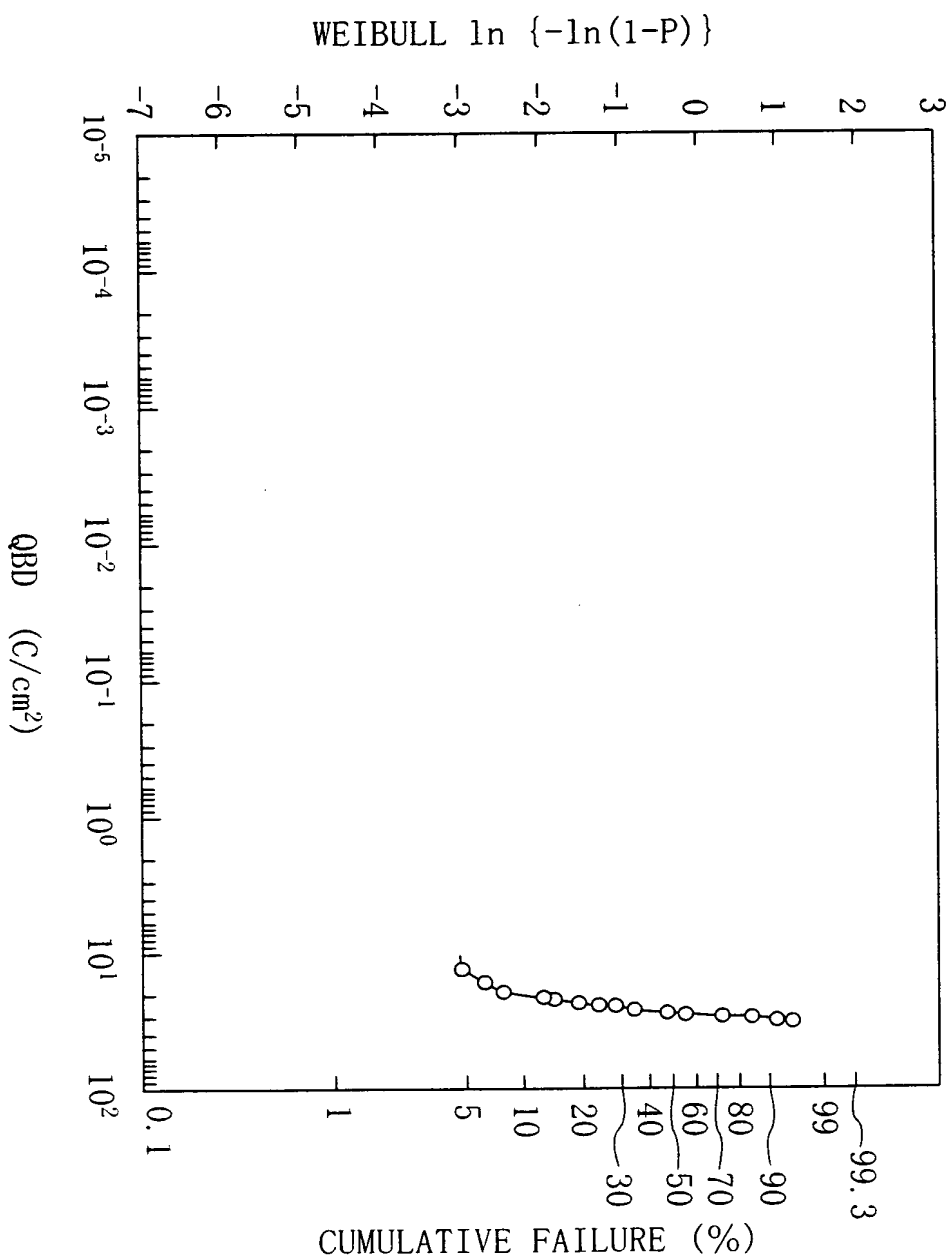
Fig. 8(d)

On polysilicon

10nm

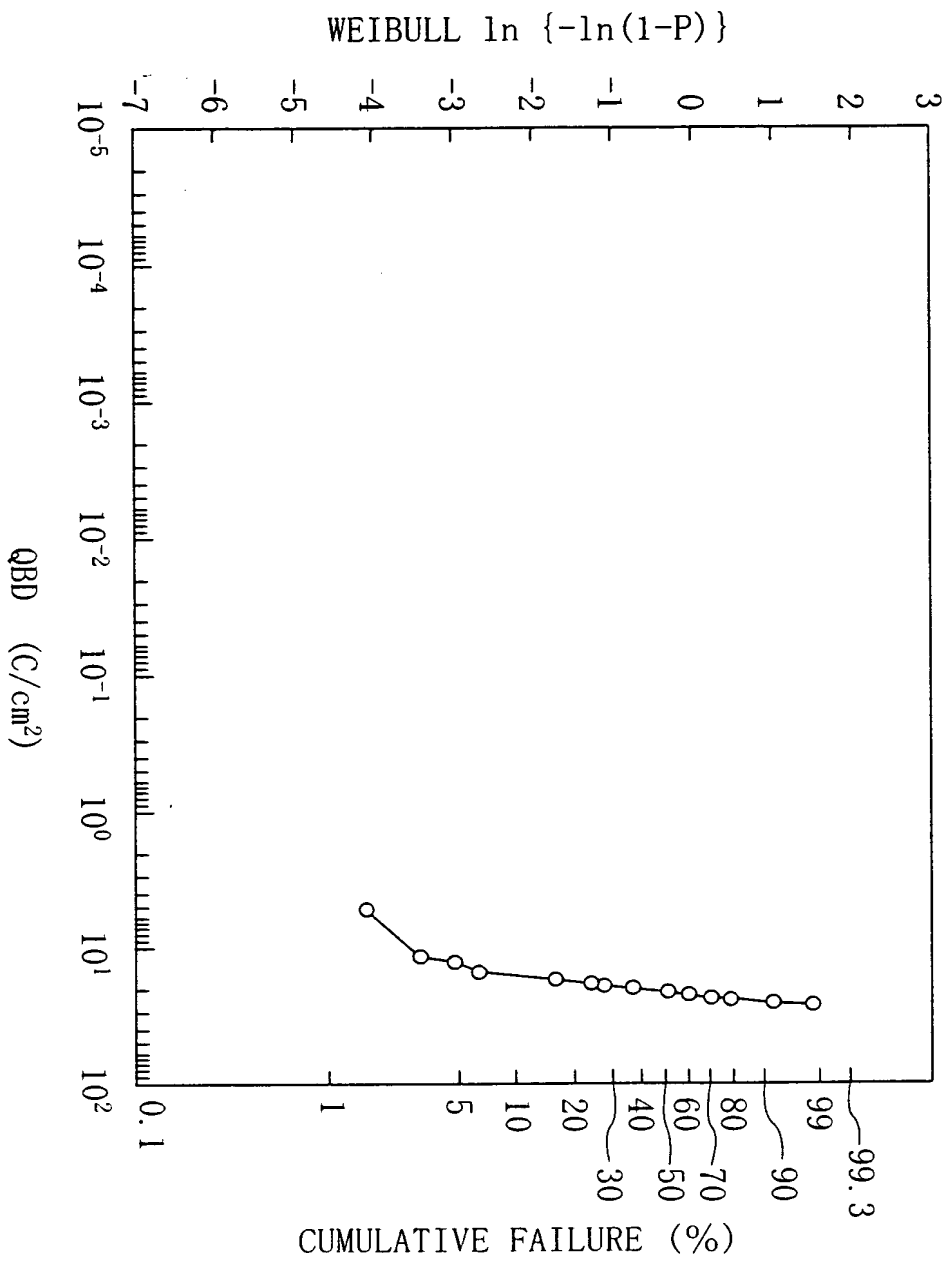


Fig. 9



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Fig. 10



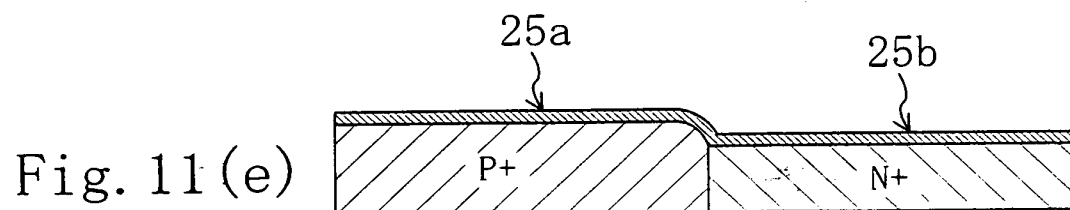
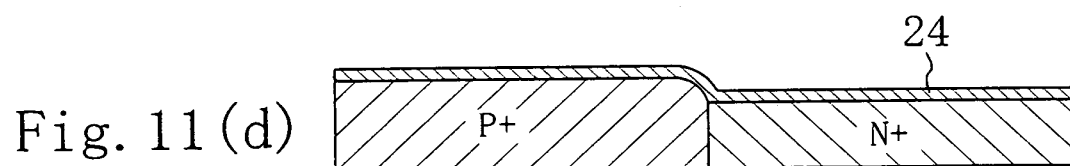
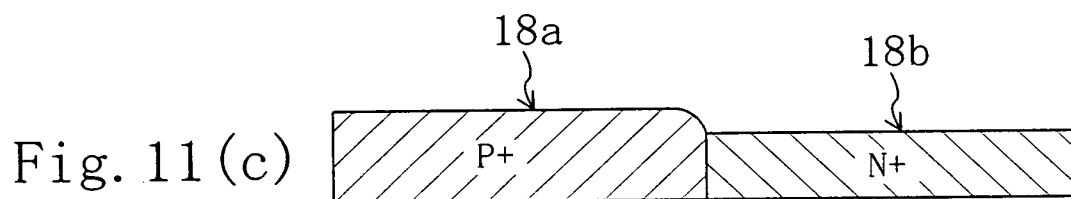
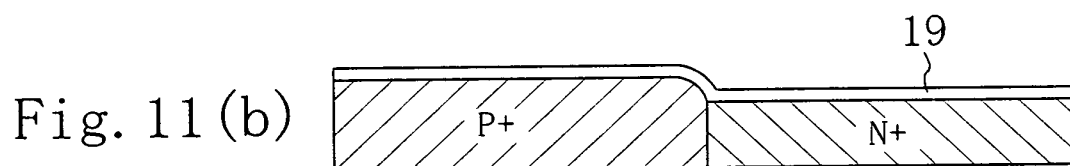
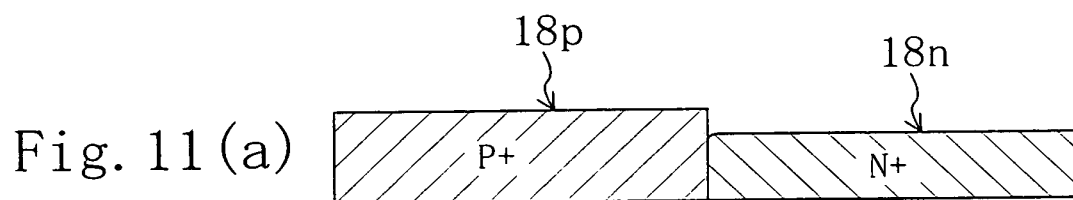


Fig. 12(a)

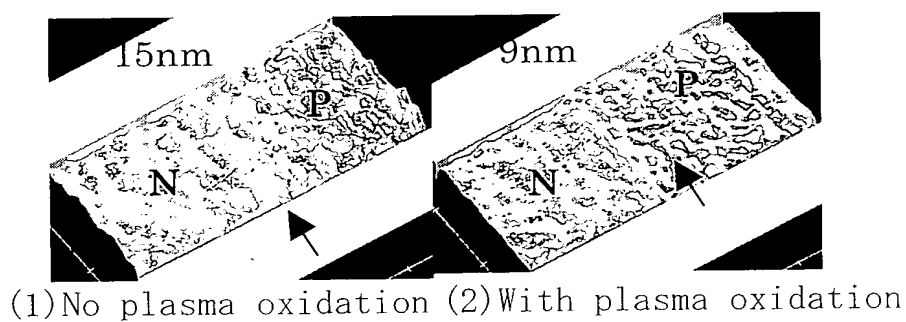
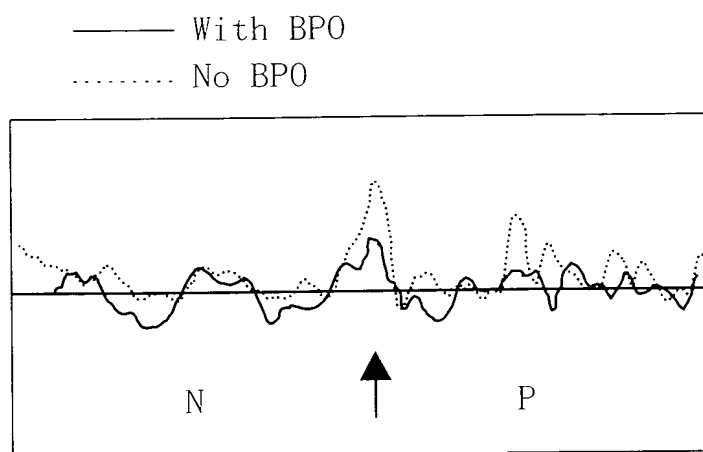
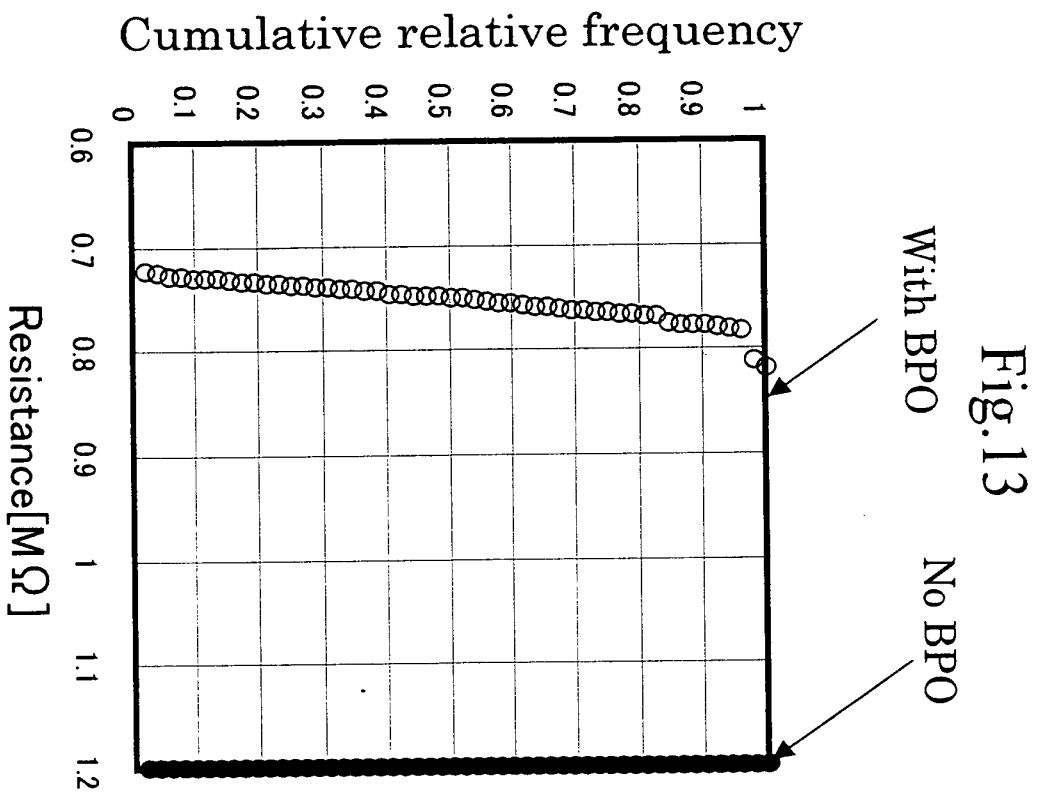


Fig. 12(b)





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Fig. 14(a)

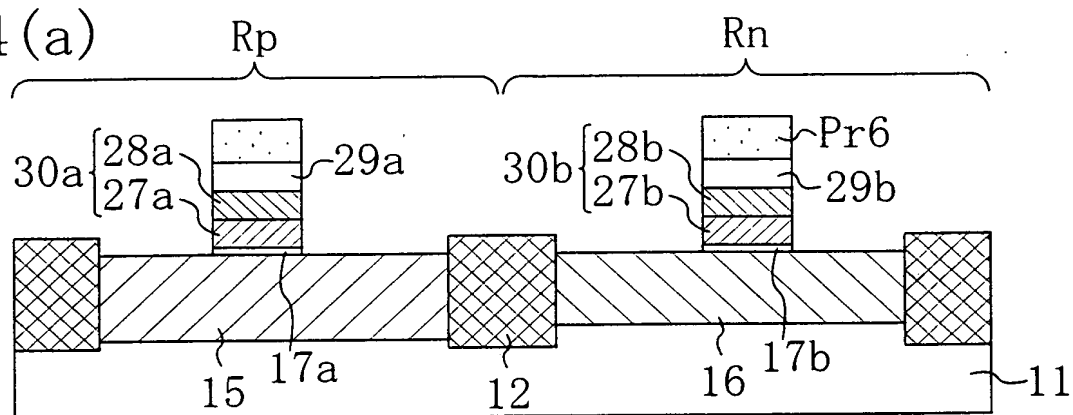


Fig. 14(b)

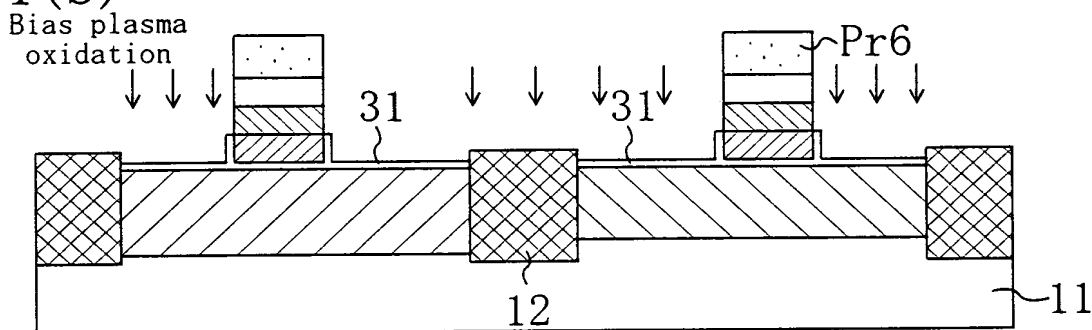


Fig. 14(c)

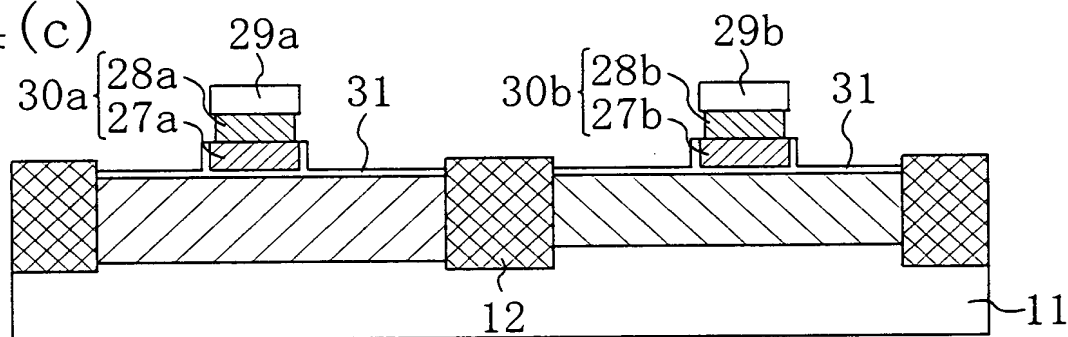
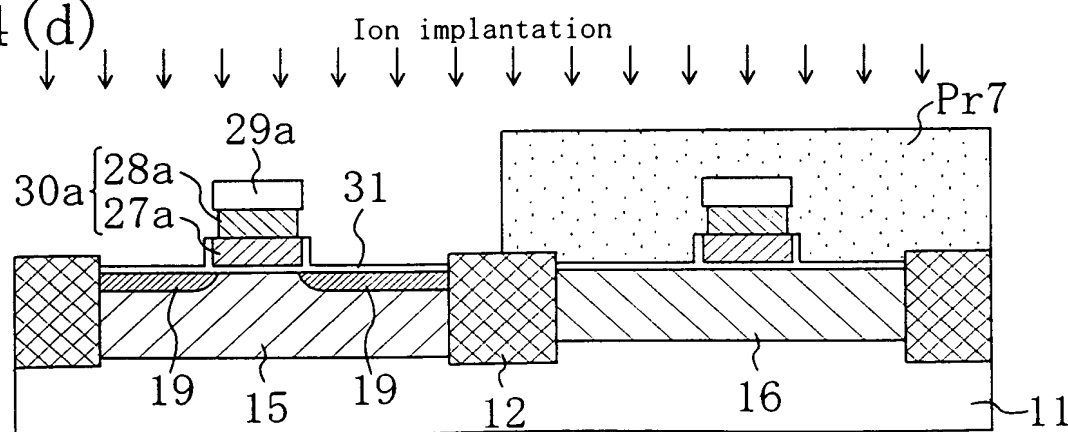


Fig. 14(d)



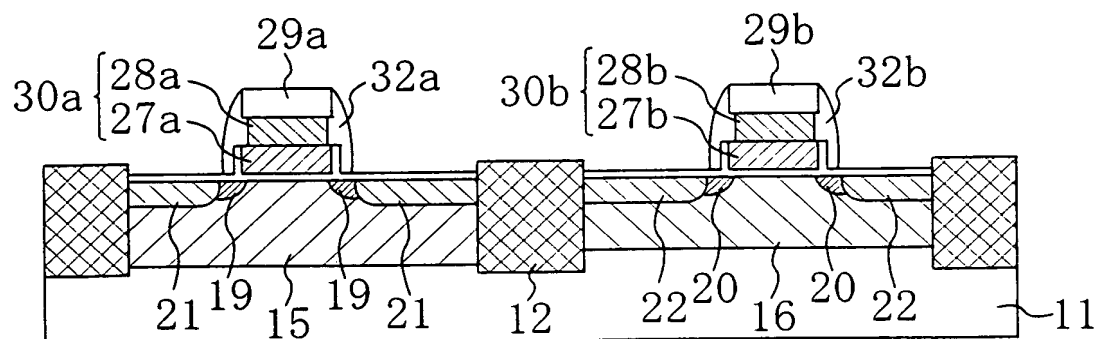
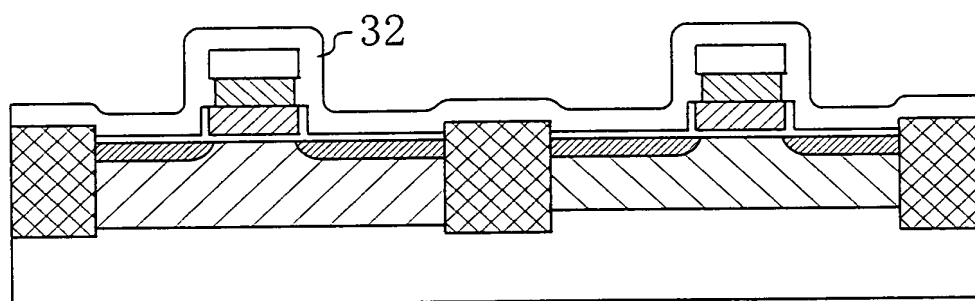
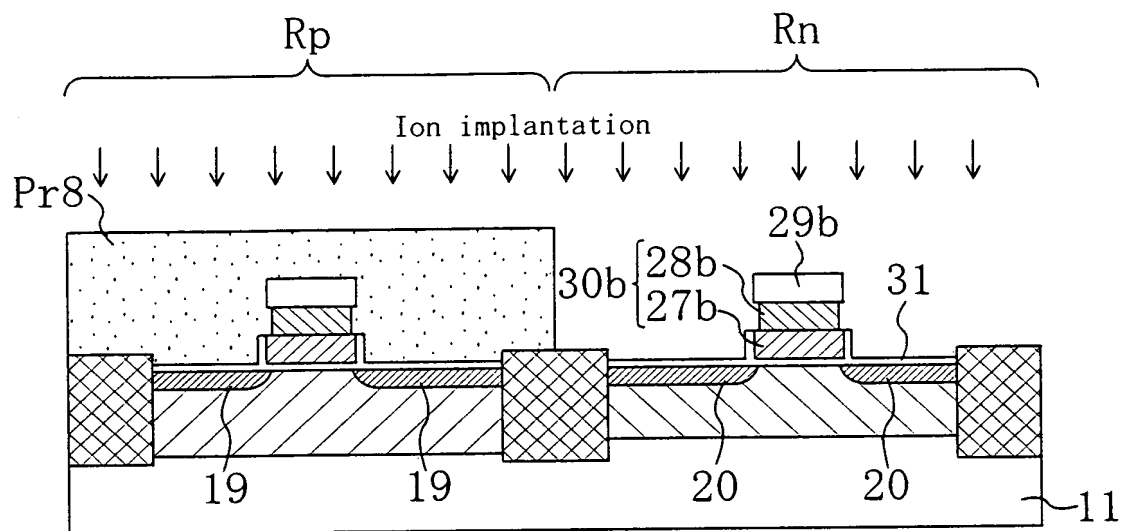
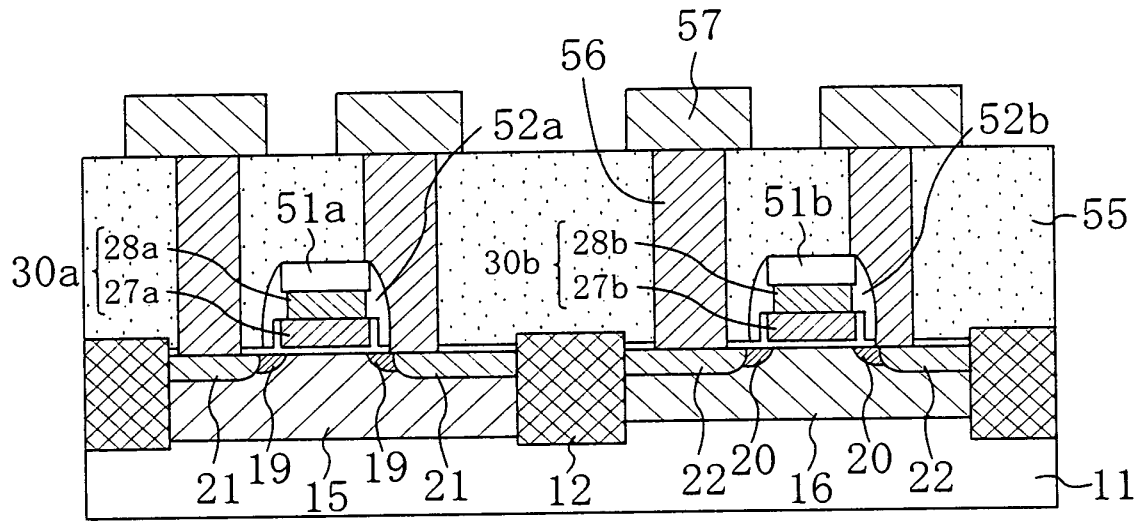


Fig. 16





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Fig. 17(a)

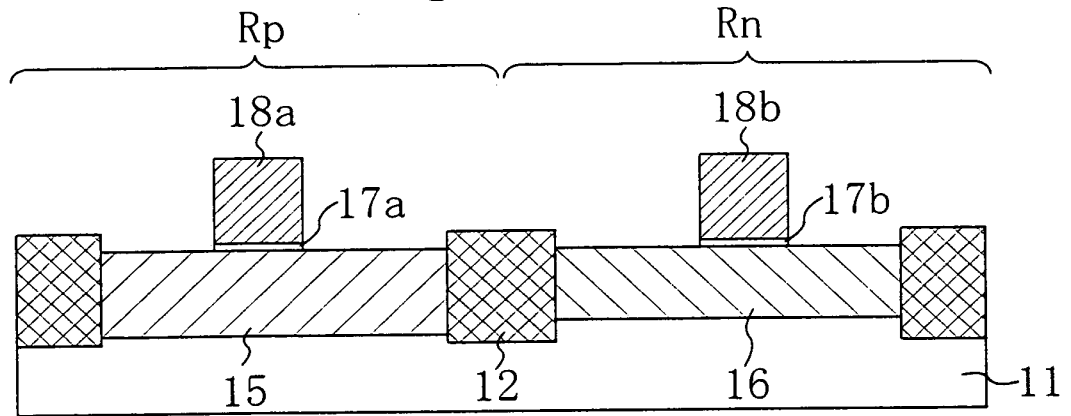


Fig. 17(b)

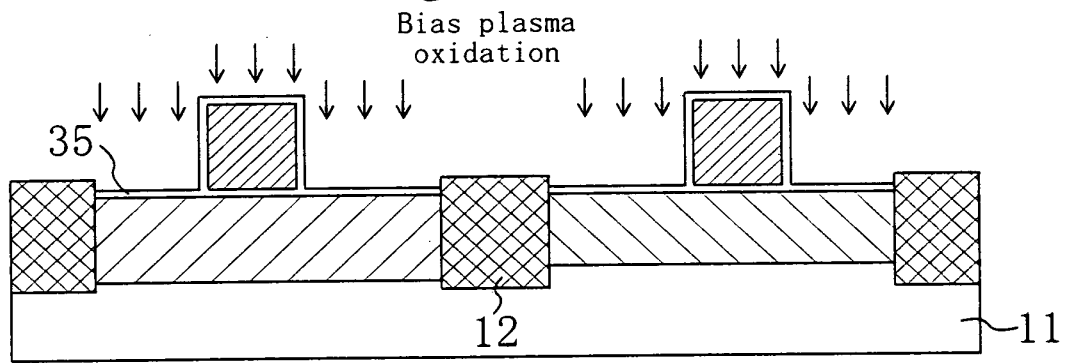


Fig. 17(c)

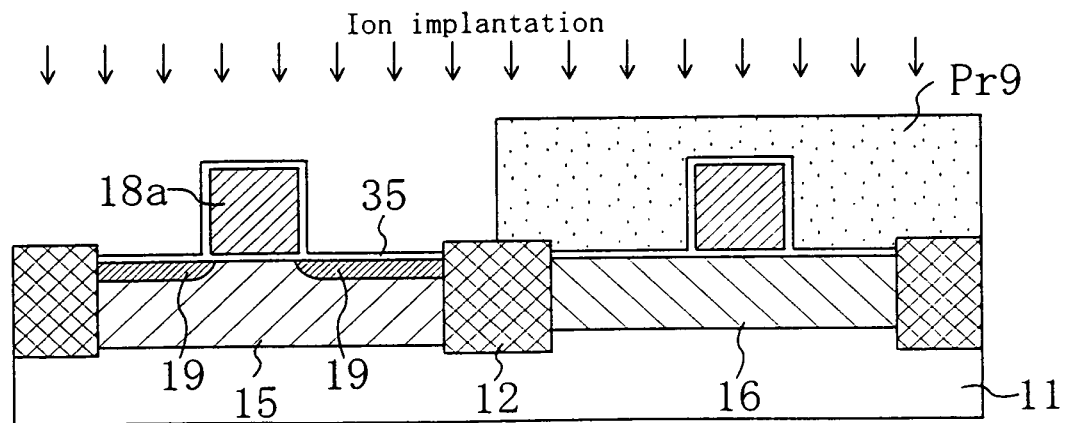


Fig. 18(a)

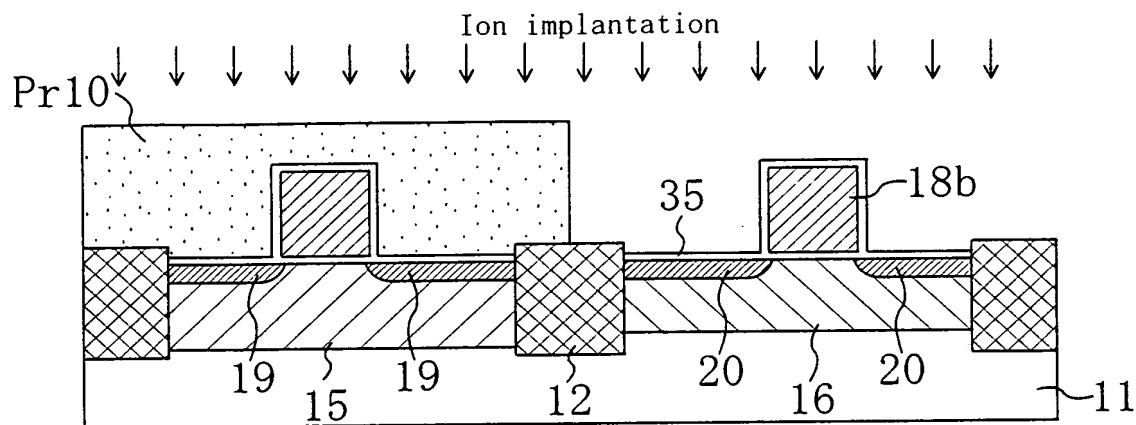


Fig. 18(b)

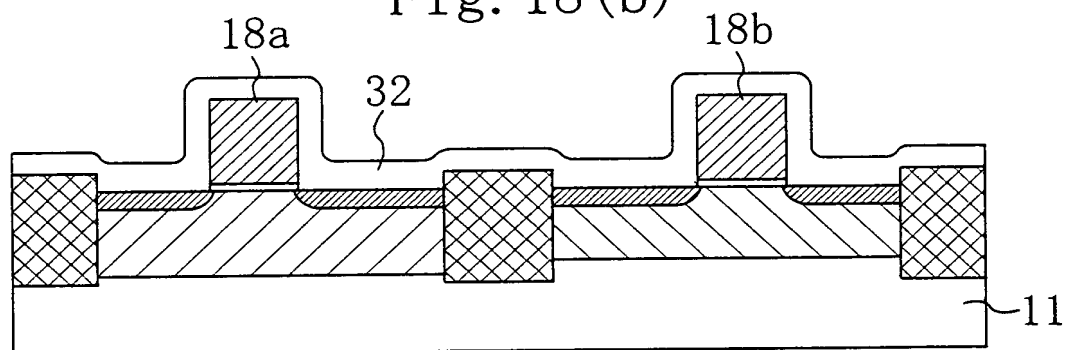


Fig. 18(c)

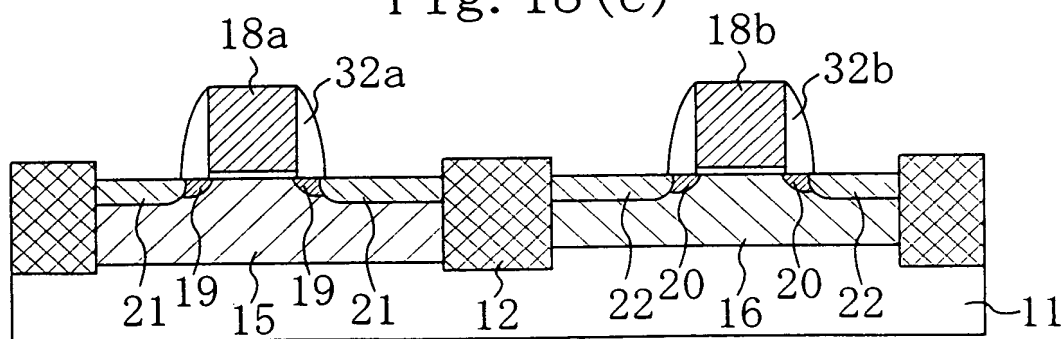


Fig. 19(a)

Pch Transistor

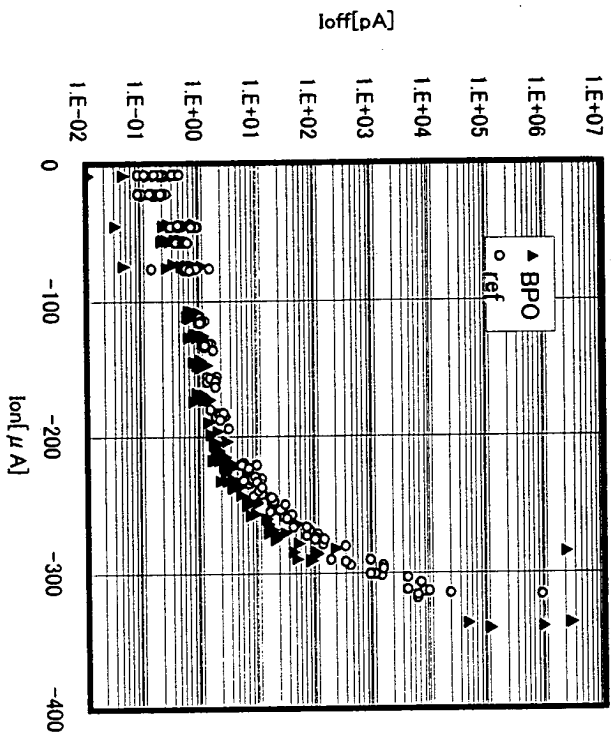
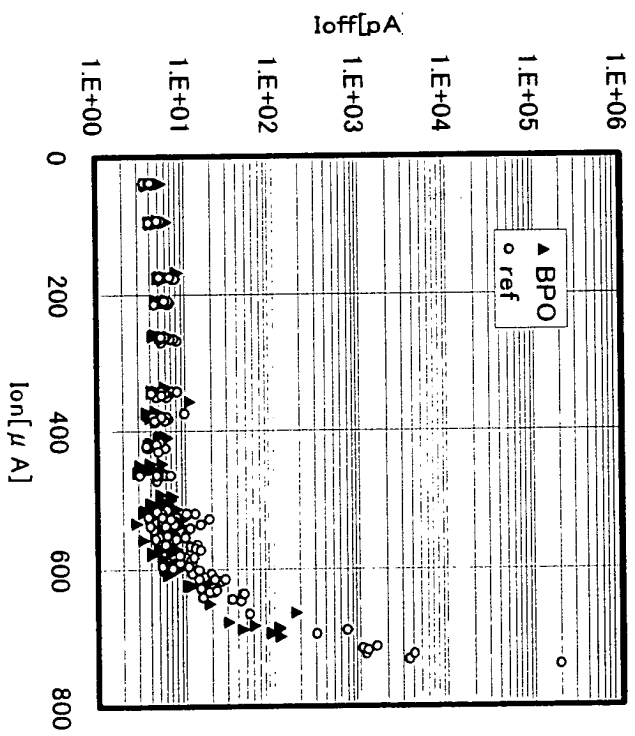


Fig. 19(b)

Nch Transistor



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Fig. 20(a)

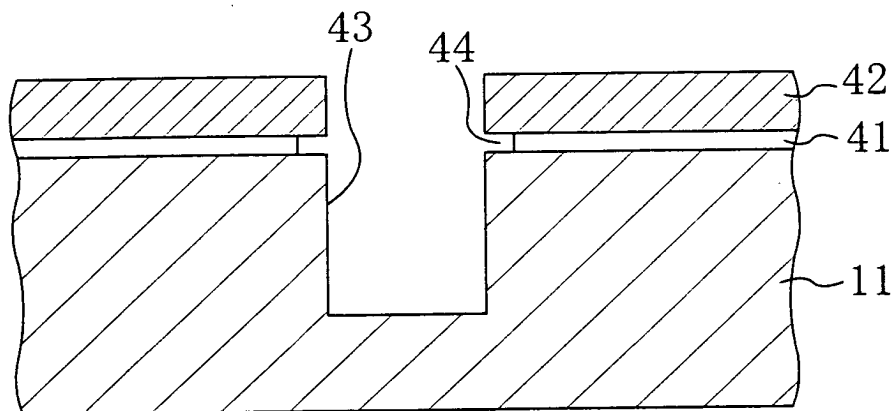


Fig. 20(b)

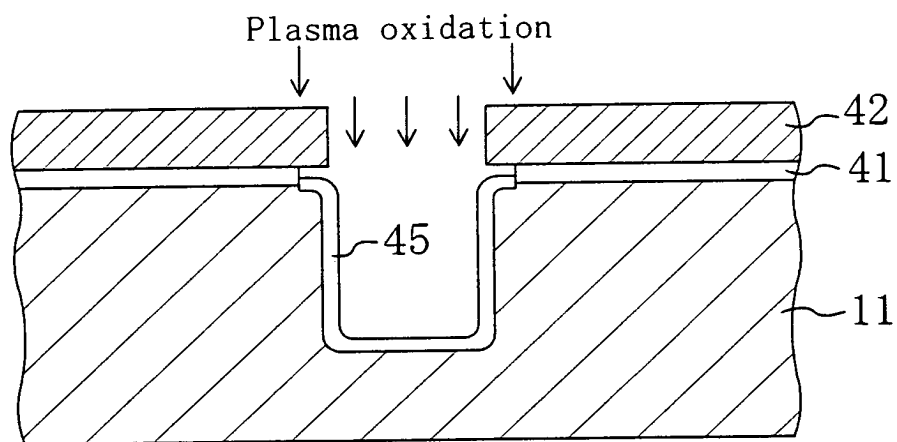


Fig. 20(c)

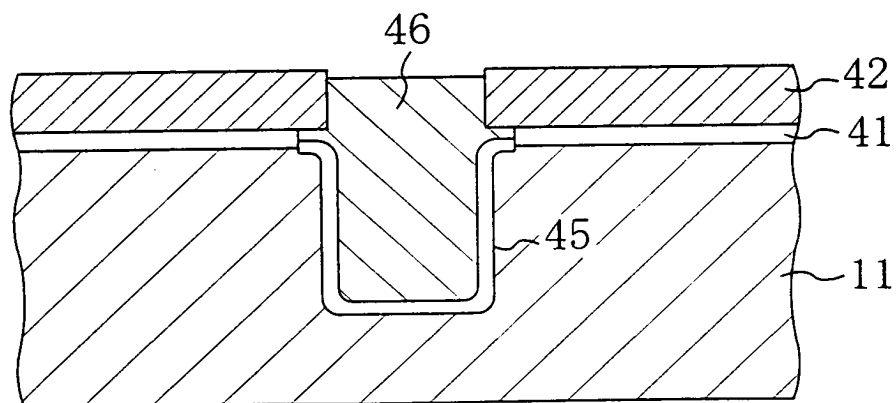


Fig. 21(a)

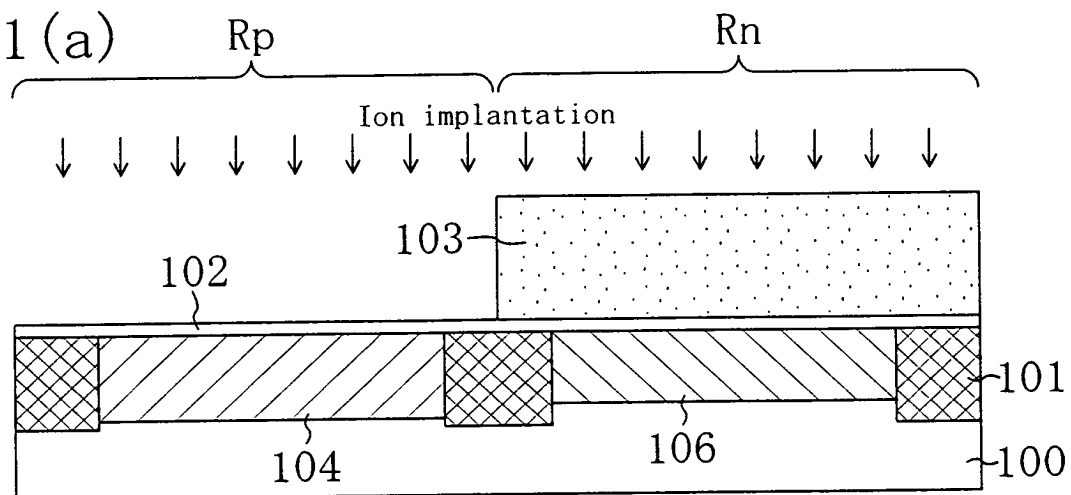


Fig. 21(b)

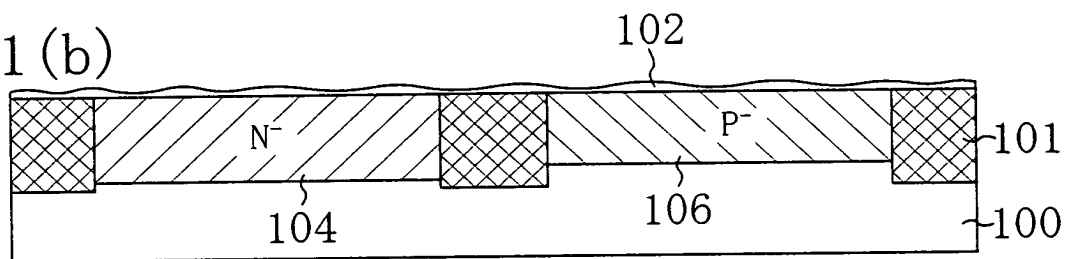


Fig. 21(c)

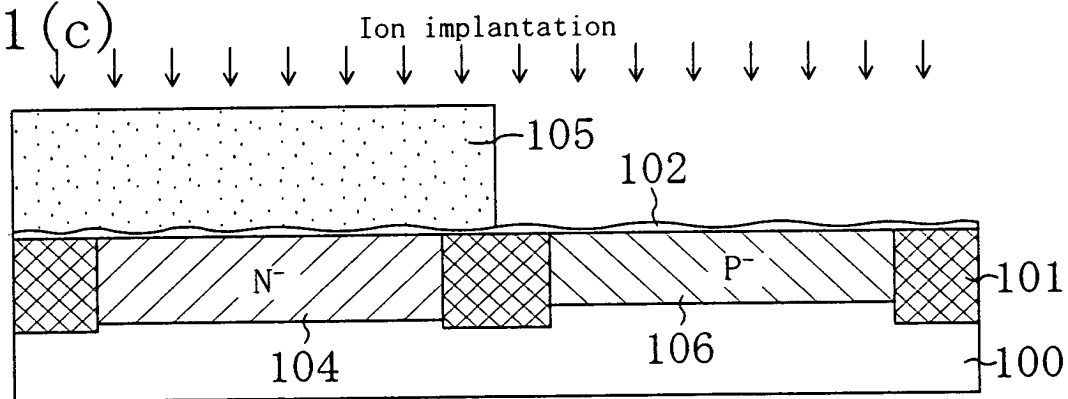


Fig. 21(d)

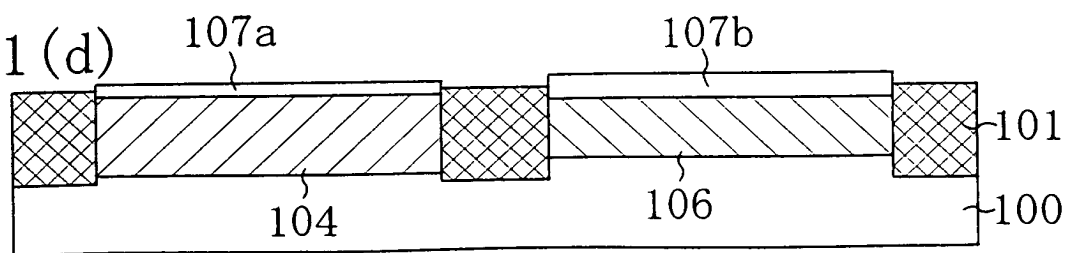


Fig. 22(a)

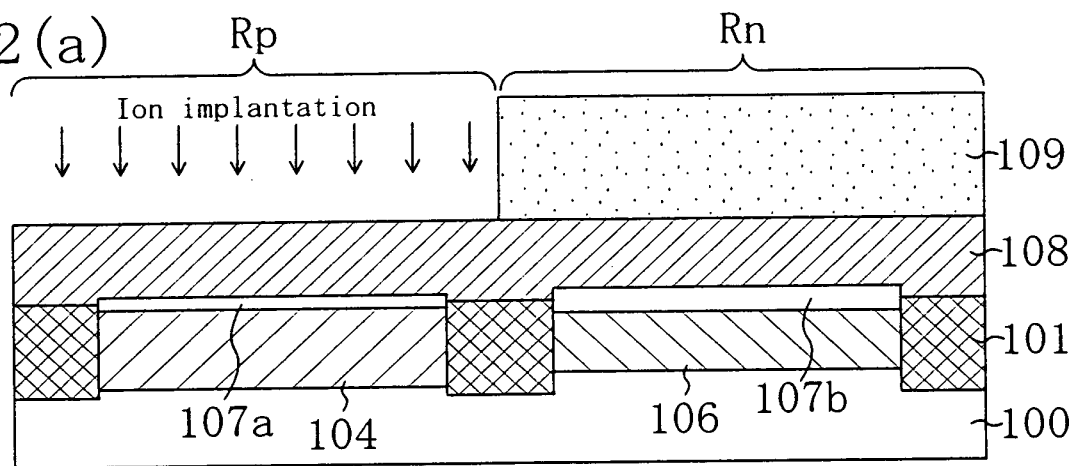


Fig. 22(b)

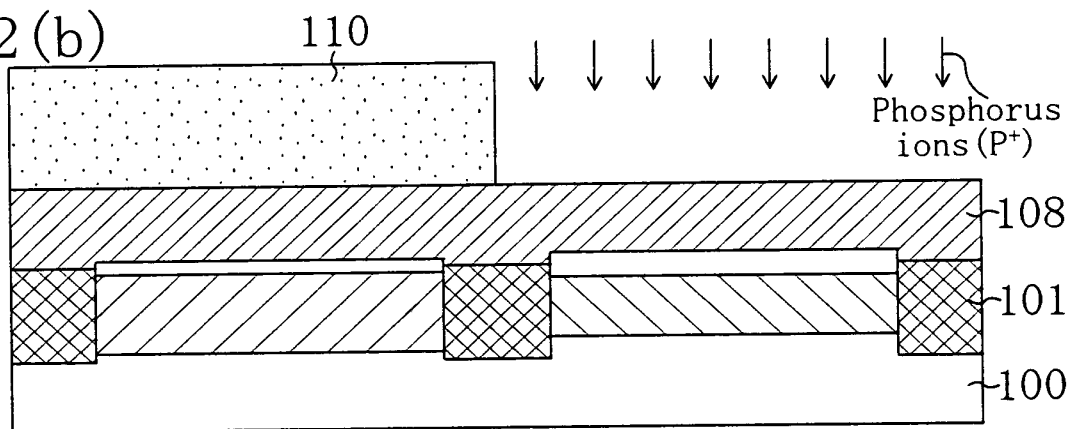


Fig. 22(c)

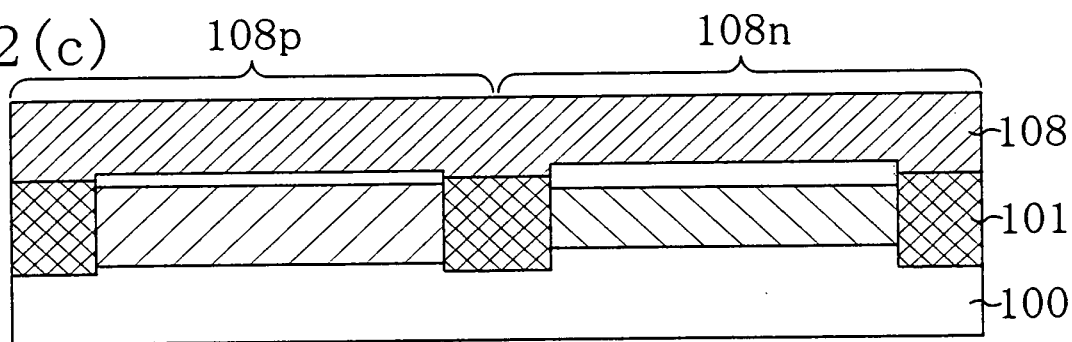
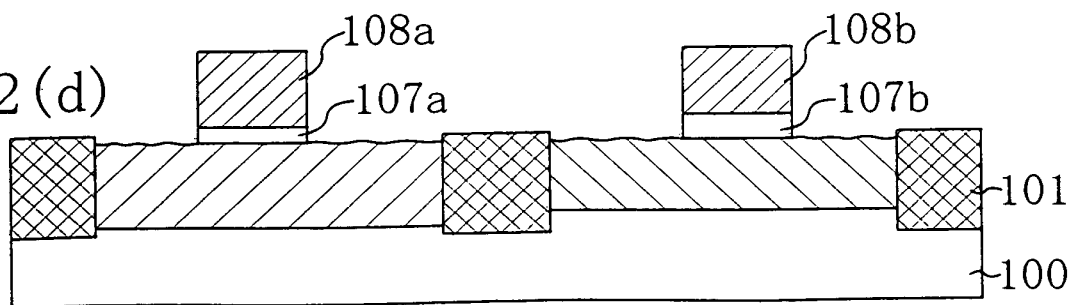


Fig. 22(d)



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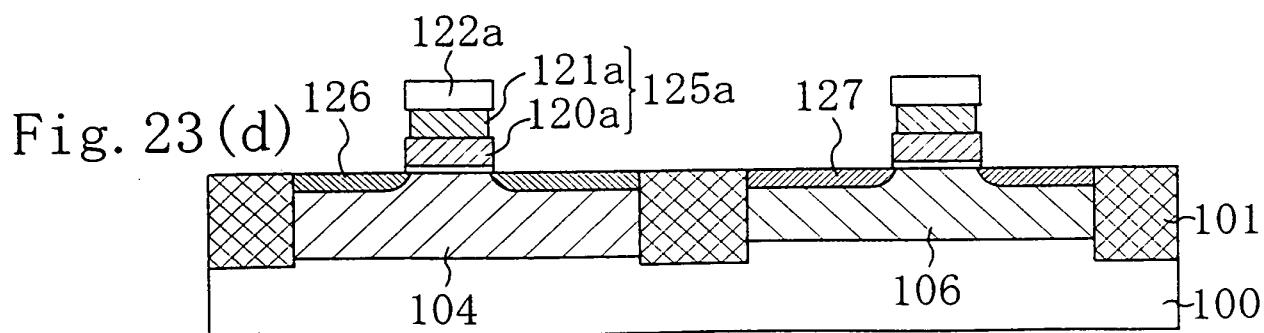
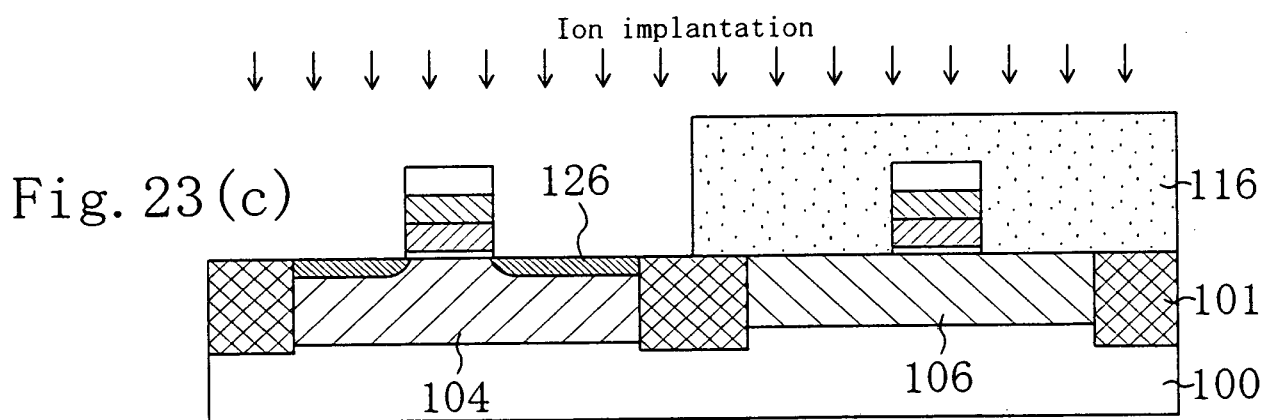
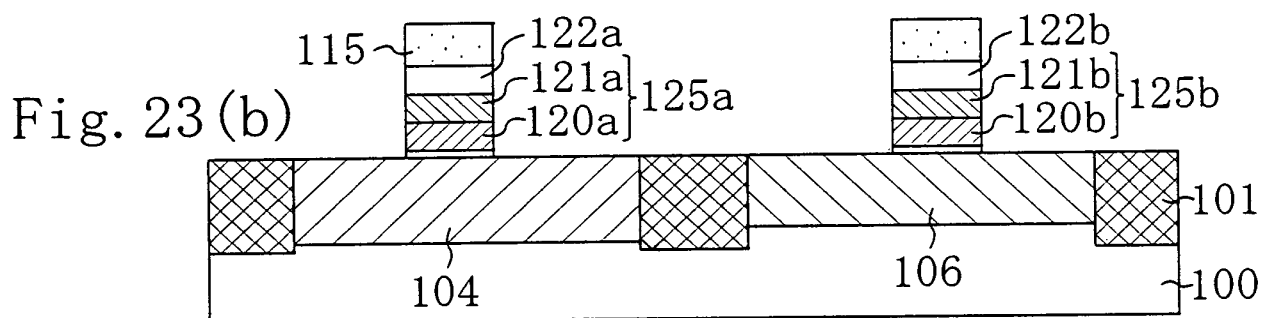
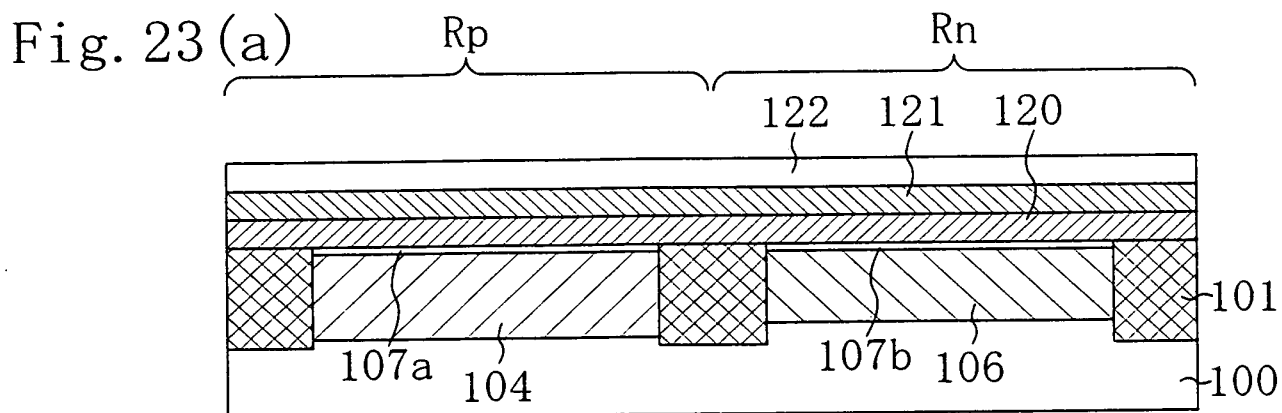


Fig. 24(a)

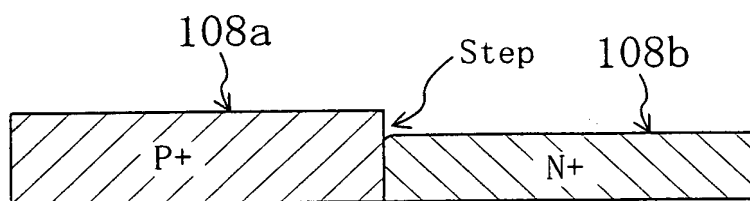


Fig. 24(b)

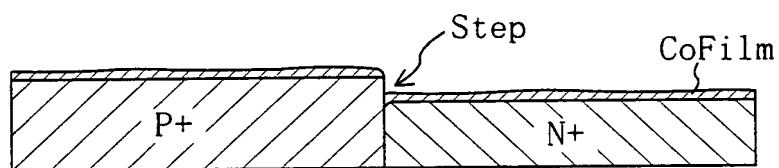


Fig. 24(c)

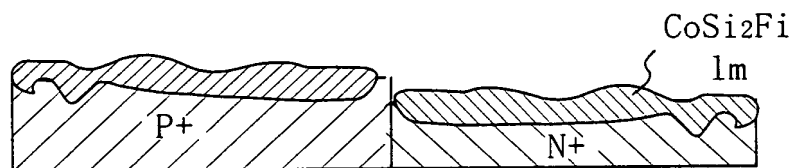


Fig. 25

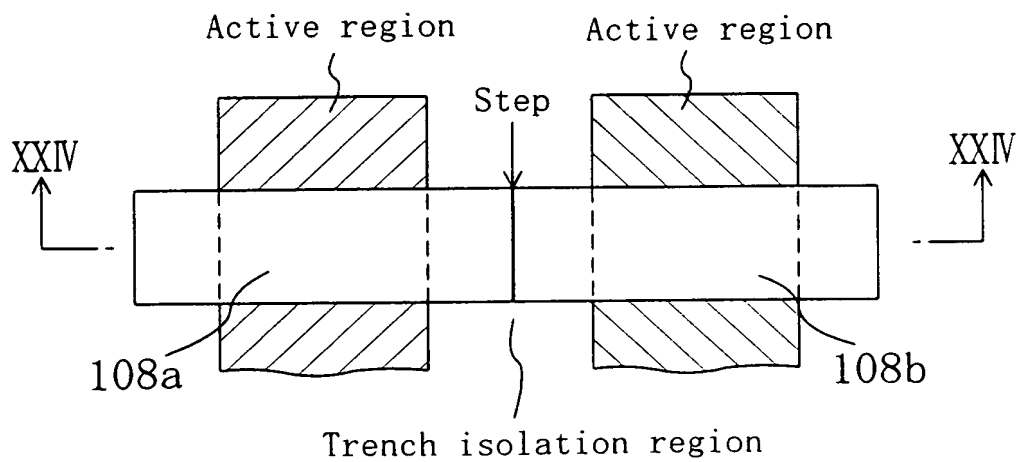
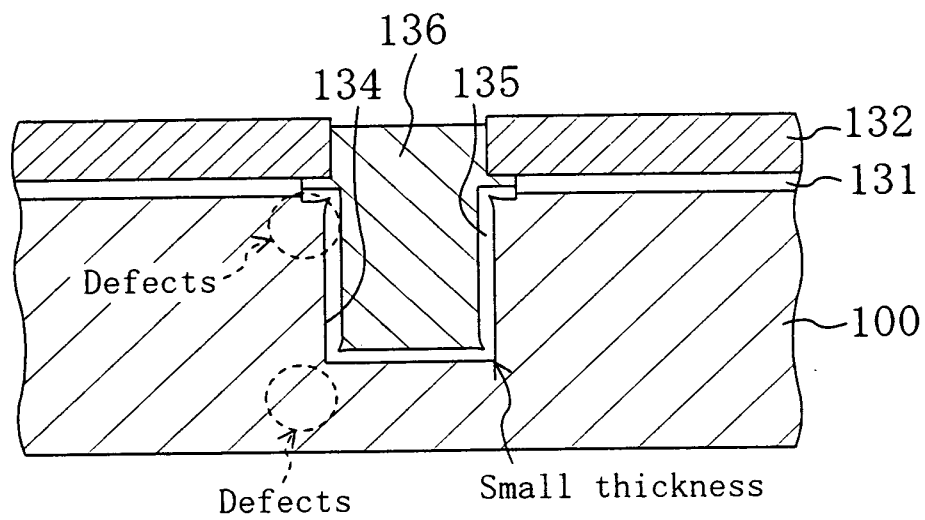




Fig. 26



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